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 August 1, 2003
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 NEWS 6 AUG 18 Data available for download as a PDF in RDISCLOSURE
 NEWS 7 AUG 18 Simultaneous left and right truncation added to PASCAL
 NEWS 8 AUG 18 FROSTI and KOSMET enhanced with Simultaneous Left and Right
 Truncation
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 NEWS 12 SEP 29 DISSABS now available on STN
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 NEWS 14 OCT 21 BIOSIS file reloaded and enhanced
 NEWS 15 OCT 28 BIOSIS file segment of TOXCENTER reloaded and enhanced

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 CA INDEXING COPYRIGHT (C) 2003 AMERICAN CHEMICAL SOCIETY (ACS)

=> s phenol novolak resin#

L1 1102 PHENOL NOVOLAK RESIN#

=> s l1 and phenol and aldehyde and oxalic and catalyst#

L2 89 L1 AND PHENOL AND ALDEHYDE AND OXALIC AND CATALYST#

=> s l2 and temperature# and pressure#

L3 81 L2 AND TEMPERATURE# AND PRESSURE#

=> s l3 and ortho ratio#

L4 1 L3 AND ORTHO RATIO#

=> d

L4 ANSWER 1 OF 1 USPATFULL on STN

Full Text	Chemical
	References

AN 2002:172464 USPATFULL

TI Method of producing novolak resin

IN Saito, Noriaki, Toyonaka-shi, JAPAN

Aizu, Ichishi, Niihama-shi, JAPAN

Nakajima, Nobuyuki, Niihama-shi, JAPAN

Fujiwara, Masahiro, Niihama-shi, JAPAN

Yano, Koji, Niihama-shi, JAPAN

PA SUMITOMO CHEMICAL COMPANY, LIMITED (non-U.S. corporation)

PI US 2002091224 A1 20020711

AI US 2001-364 A1 20011204 (10)

PRAI JP 2000-377258 20001212

JP 2000-377259 20001212

JP 2001-153632 20010523

DT Utility

FS APPLICATION

LN.CNT 579

INCL INCLM: 528/129.000

NCL NCLM: 528/129.000

IC [7]

ICM: C08G008-04

CAS INDEXING IS AVAILABLE FOR THIS PATENT.

=> s l3 and ortho

L5 25 L3 AND ORTHO

=> s l5 and (ortho-cresol or o-cresol)

L6 14 L5 AND (ORTHO-CRESOL OR O-CRESOL)

=> d l6 1-14

L6 ANSWER 1 OF 14 EUROPATFULL COPYRIGHT 2003 WILA on STN

Full Text

PATENT APPLICATION - PATENTANMELDUNG - DEMANDE DE BREVET

AN 720052 EUROPATFULL UP 19970408 EW 199627 FS OS STA R

TIEN Photosensitive composition and photosensitive lithographic printing plate.

TIDE Photoempfindliche Zusammensetzung und photolithographische Druckplatte.

TIFR Composition photosensible et plaque d'impression photolithographique.

IN Matsuo, Fumijuku, Yokohama Research Center, Mitsubishi Chemical Corp.,

1000, Kamoshida-cho, Aoba-ku, Yokohama-shi, Kanagawa 227, JP;
 Kanazawa, Daisuke, Yokohama Research Center, Mitsubishi Chemical Corp.,
 1000, Kamoshida-cho, Aoba-ku, Yokohama-shi, Kanagawa 227, JP;
 Sasaki, Mitsuru, Yokohama Research Center, Mitsubishi Chemical Corp.,
 1000, Kamoshida-cho, Aoba-ku, Yokohama-shi, Kanagawa 227, JP;
 Matsubara, Shinichi, Konica Corp., 1, Sakura-machi, Hino-shi, Tokyo, JP;
 Higashino, Katsuhiko, Konica Corp., 1, Sakura-machi, Hino-shi, Tokyo,
 JP;
 Yokoo, Toshiaki, Yokohama Research Center, Mitsubishi Chemical Corp.,
 1000, Kamoshida-cho, Aoba-ku, Yokohama-shi, Kanagawa 227, JP
 PA Mitsubishi Chemical Corporation, 5-2 Marunouchi 2-chome, Chiyoda-ku,
 Tokyo, JP KONICA CORPORATION, No. 1 Sakura-machi, Hino-shi Tokyo, JP
 SO Wila-EPZ-1996-H27-T2a
 DS R DE; R FR; R GB; R NL
 PIT EPAL EUROPÄISCHE PATENTANMELDUNG
 PI EP 720052 A1 19960703
 OD 19960703
 AI EP 1995-119982 19951218
 PRAI JP 1994-337070 19941227
 JP 1995-692 19950106
 IC ICM G03F007-023

L6 ANSWER 2 OF 14 EUROPATFULL COPYRIGHT 2003 WILA on STN

Full
Text

PATENT APPLICATION - PATENTANMELDUNG - DEMANDE DE BREVET

AN 660187 EUROPATFULL UP 19991205 EW 199526 FS OS STA B
 TIEN Radiation-sensitive resin composition.
 TIDE Strahlungsempfindliche Harzzusammensetzung.
 TIFR Composition a base de resine, sensible aux radiations.
 IN Yamachika, Mikio, 15-1-1105, Taichimaru, Kuwana-shi, JP;
 Kobayashi, Eiichi, 535 Pierce St. No.336, Albany, CA 94706, US;
 Ota, Toshiyuki, 208, Unemegaoka-4-chome, Yokkaichi-shi, JP;
 Tsuji, Akira, 3-7, Hagigaokacho, Yokkaichi-shi, JP
 PA JAPAN SYNTHETIC RUBBER CO., LTD., 11-24, Tsukiji-2-chome Chuo-ku, Tokyo
 104, JP
 SO Wila-EPZ-1995-H26-T2a
 DS R DE; R FR; R GB; R IT; R NL
 PIT EPAL EUROPÄISCHE PATENTANMELDUNG
 PI EP 660187 A1 19950628
 OD 19950628
 AI EP 1994-309457 19941216
 PRAI JP 1993-345792 19931224
 JP 1994-268112 19941007
 IC ICM G03F007-039

GRANTED PATENT - ERTEILTES PATENT - BREVET DELIVRE

AN 660187 EUROPATFULL ED 19970414 EW 199710 FS PS
 TIEN Radiation-sensitive resin composition.
 TIDE Strahlungsempfindliche Harzzusammensetzung.
 TIFR Composition a base de resine, sensible aux radiations.
 IN Yamachika, Mikio, 15-1-1105, Taichimaru, Kuwana-shi, JP;
 Kobayashi, Eiichi, 535 Pierce St. No.336, Albany, CA 94706, US;
 Ota, Toshiyuki, 208, Unemegaoka-4-chome, Yokkaichi-shi, JP;
 Tsuji, Akira, 3-7, Hagigaokacho, Yokkaichi-shi, JP
 PA JAPAN SYNTHETIC RUBBER CO., LTD., 11-24, Tsukiji-2-chome Chuo-ku, Tokyo
 104, JP
 SO Wila-EPS-1997-H10-T2
 DS R DE; R FR; R GB; R IT; R NL
 PIT EPB1 EUROPÄISCHE PATENTSCHRIFT
 PI EP 660187 B1 19970305

OD 19950628
 AI EP 1994-309457 19941216
 PRAI JP 1993-345792 19931224
 JP 1994-268112 19941007
 REN DATABASE WPI Section Ch, Week 9323, Derwent Publications Ltd., London, GB; Class A89, AN 93-185601 & JP-A-5113667 (MITSUBISHI ELECTRIC CORP) 7 May 1993 DATABASE WPI Section Ch, Week 9322, Derwent Publications Ltd., London, GB; Class A13, AN 93-177961 & JP-A-5107757 (CANON KK) 30 April 1993
 IC ICM G03F007-039

L6 ANSWER 3 OF 14 EUROPATFULL COPYRIGHT 2003 WILA on STN

Full
Text

PATENT APPLICATION - PATENTANMELDUNG - DEMANDE DE BREVET

AN 591984 EUROPATFULL UP 20000216 EW 199415 FS OS STA B
 TIEN Resin composition for aqueous paint.
 TIDE Harzzusammensetzung fuer einen waessrigen Anstrich.
 TIFR Composition de resine pour une peinture aqueuse.
 IN Fujibayashi, Toshio, 944-8, Imaizumi, Hadano-shi, Kanagawa-ken, JP; Nagaoka, Haruo, 776-7, Hirokawa, Hiratsuka-shi, Kanagawa-ken, JP
 PA KANSAI PAINT CO. LTD., 33-1, Kanzaki-cho, Amagasaki-shi Hyogo-ken, JP
 SO Wila-EPZ-1994-H15-T1a
 DS R DE; R GB
 PIT EPA1 EUROPAEISCHE PATENTANMELDUNG
 PI EP 591984 A1 19940413
 OD 19940413
 AI EP 1993-116319 19931008
 PRAI JP 1992-297953 19921009
 JP 1993-32538 19930129
 JP 1993-32587 19930129
 IC ICM C09D005-44
 ICS C08G059-64

GRANTED PATENT - ERTEILTES PATENT - BREVET DELIVRE

AN 591984 EUROPATFULL ED 19970727 EW 199728 FS PS
 TIEN Resin composition for aqueous paint.
 TIDE Harzzusammensetzung fuer einen waessrigen Anstrich.
 TIFR Composition de resine pour une peinture aqueuse.
 IN Fujibayashi, Toshio, 944-8, Imaizumi, Hadano-shi, Kanagawa-ken, JP; Nagaoka, Haruo, 776-7, Hirokawa, Hiratsuka-shi, Kanagawa-ken, JP
 PA KANSAI PAINT CO. LTD., 33-1, Kanzaki-cho, Amagasaki-shi Hyogo-ken, JP
 SO Wila-EPS-1997-H28-T1
 DS R DE; R GB
 PIT EPB1 EUROPAEISCHE PATENTSCHRIFT
 PI EP 591984 B1 19970709
 OD 19940413
 AI EP 1993-116319 19931008
 PRAI JP 1992-297953 19921009
 JP 1993-32538 19930129
 JP 1993-32587 19930129
 REP EP 356970 A EP 444710 A
 US 5091446 A
 IC ICM C09D005-44
 ICS C08G059-64

L6 ANSWER 4 OF 14 EUROPATFULL COPYRIGHT 2003 WILA on STN

Full
Text

PATENT APPLICATION - PATENTANMELDUNG - DEMANDE DE BREVET

AN 567066 EUROPATFULL ED 20000416 EW 199343 FS OS STA B
 TIEN Resin composition for aqueous paints.
 TIDE Harzzusammensetzung fuer waessrige Lacke.
 TIFR Composition de resine pour des peintures aqueuses.
 IN Fujibayashi, Toshio, 944-8, Imaizumi, Hadano-shi, Kanagawa-ken, JP;
 Nagaoka, Haruo, 776-7, Hirokawa, Hiratsuka-shi, Kanagawa-ken, JP
 PA KANSAI PAINT CO. LTD., 33-1, Kanzaki-cho, Amagasaki-shi Hyogo-ken, JP
 SO Wila-EPZ-1993-H43-T1a
 DS R DE; R GB
 PIT EPA2 EUROPAEISCHE PATENTANMELDUNG
 PI EP 567066 A2 19931027
 OD 19931027
 AI EP 1993-106378 19930420
 PRAI JP 1992-129740 19920424
 IC ICM C09D005-44
 ICS C09D163-00 C08G059-62 C08G059-64

GRANTED PATENT - ERTEILTES PATENT - BREVET DELIVRE

AN 567066 EUROPATFULL UP 20000723 EW 200028 FS PS
 TIEN Resin composition for aqueous paints.
 TIDE Harzzusammensetzung fuer waessrige Lacke.
 TIFR Composition de resine pour des peintures aqueuses.
 IN Fujibayashi, Toshio, 944-8, Imaizumi, Hadano-shi, Kanagawa-ken, JP;
 Nagaoka, Haruo, 776-7, Hirokawa, Hiratsuka-shi, Kanagawa-ken, JP
 PA KANSAI PAINT CO. LTD., 33-1, Kanzaki-cho, Amagasaki-shi Hyogo-ken, JP
 SO Wila-EPS-2000-H28-T1
 DS R DE; R GB
 PIT EPB1 EUROPAEISCHE PATENTSCHRIFT
 PI EP 567066 B1 20000712
 OD 19931027
 AI EP 1993-106378 19930420
 PRAI JP 1992-129740 19920424
 REP EP 127915 A EP 135811 A
 EP 352671 A EP 396912 A
 EP 591984 A
 IC ICM C09D005-44
 ICS C09D163-00 C08G059-62 C08G059-64 C08G059-32

L6 ANSWER 5 OF 14 USPATFULL on STN

Full Text	Citing References
-----------	-------------------

AN 2002:172464 USPATFULL
 TI Method of producing novolak resin
 IN Saito, Noriaki, Toyonaka-shi, JAPAN
 Aizu, Ichishi, Niihama-shi, JAPAN
 Nakajima, Nobuyuki, Niihama-shi, JAPAN
 Fujiwara, Masahiro, Niihama-shi, JAPAN
 Yano, Koji, Niihama-shi, JAPAN
 PA SUMITOMO CHEMICAL COMPANY, LIMITED (non-U.S. corporation)
 PI US 2002091224 A1 20020711
 AI US 2001-364 A1 20011204 (10)
 PRAI JP 2000-377258 20001212
 JP 2000-377259 20001212
 JP 2001-153632 20010523
 DT Utility
 FS APPLICATION
 LN.CNT 579
 INCL INCLM: 528/129.000
 NCL NCLM: 528/129.000
 IC [7]
 ICM: C08G008-04

CAS INDEXING IS AVAILABLE FOR THIS PATENT.

L6 ANSWER 6 OF 14 USPATFULL on STN

Full Text	Citing References
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AN 2001:165552 USPATFULL
 TI Phenol novolak resin, production process thereof, and positive photoresist composition using the same
 IN Miyagi, Ken, Kanagawa, Japan
 Ohuchi, Yasuhide, Kanagawa, Japan
 Hirata, Atsuko, Kanagawa, Japan
 Doi, Kousuke, Kanagawa, Japan
 Kohara, Hidekatsu, Kanagawa, Japan
 Nakayama, Toshimasa, Kanagawa, Japan
 PI US 2001024762 A1 20010927
 AI US 2001-793958 A1 20010228 (9)
 PRAI JP 2000-53503 20000229
 JP 2000-53504 20000229
 JP 2000-53505 20000229
 DT Utility
 FS APPLICATION
 LN.CNT 1209
 INCL INCLM: 430/192.000
 INCLS: 430/165.000; 430/191.000; 430/193.000; 430/326.000; 528/155.000;
 528/144.000
 NCL NCLM: 430/192.000
 NCLS: 430/165.000; 430/191.000; 430/193.000; 430/326.000; 528/155.000;
 528/144.000
 IC [7]
 ICM: G03F007-023
 ICS: C08G014-04; G03F007-30

CAS INDEXING IS AVAILABLE FOR THIS PATENT.

L6 ANSWER 7 OF 14 USPATFULL on STN

Full Text	Citing References
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AN 1998:4379 USPATFULL
 TI Positive resin composition sensitive to ultraviolet rays
 IN Kawabe, Yasumasa, Haibara-gun, Japan
 Yamanaka, Tsukasa, Haibara-gun, Japan
 Aoai, Toshiaki, Haibara-gun, Japan
 PA Fuji Photo Film Co., LTD., Kanagawa, Japan (non-U.S. corporation)
 PI US 5707776 19980113
 AI US 1995-438481 19950510 (8)
 PRAI JP 1994-98671 19940512
 DT Utility
 FS Granted
 LN.CNT 1881
 INCL INCLM: 430/270.100
 INCLS: 430/920.000; 430/921.000; 430/905.000; 430/171.000; 430/176.000;
 522/166.000
 NCL NCLM: 430/270.100
 NCLS: 430/171.000; 430/176.000; 430/905.000; 430/920.000; 430/921.000;
 522/166.000
 IC [6]
 ICM: G03C001-73
 EXF 430/270; 430/920; 430/921; 430/905; 430/171; 430/176; 522/166
 CAS INDEXING IS AVAILABLE FOR THIS PATENT.

L6 ANSWER 8 OF 14 USPATFULL on STN

Full Text	Citing References
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AN 97:59033 USPATFULL
 TI Photosensitive composition and photosensitive lithographic printing

plate
 IN Matsuo, Fumiyuki, Yokohama, Japan
 Kanazawa, Daisuke, Yokohama, Japan
 Sasaki, Mitsuru, Yokohama, Japan
 Matsubara, Shinichi, Hino, Japan
 Higashino, Katsuhiko, Hino, Japan
 Yokoo, Toshiaki, Yokohama, Japan
 PA Mitsubishi Chemical Corporation, Tokyo, Japan (non-U.S. corporation)
 Konica Corporation, Tokyo, Japan (non-U.S. corporation)
 PI US 5645969 19970708
 AI US 1995-576136 19951221 (8)
 PRAI JP 1994-337070 19941227
 JP 1995-692 19950106
 DT Utility
 FS Granted
 LN.CNT 1292
 INCL INCLM: 430/165.000
 INCLS: 430/190.000; 430/191.000; 430/192.000; 430/193.000; 528/137.000;
 528/139.000
 NCL NCLM: 430/165.000
 NCLS: 430/190.000; 430/191.000; 430/192.000; 430/193.000; 528/137.000;
 528/139.000
 IC [6]
 ICM: G03F007-023
 EXF 430/190; 430/165; 430/192; 430/193; 430/191; 528/137; 528/139
 CAS INDEXING IS AVAILABLE FOR THIS PATENT.

L6 ANSWER 9 OF 14 USPATFULL on STN

Full Text	Citing References
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AN 96:85015 USPATFULL
 TI Radiation sensitive resin composition comprising copolymer of
 isopropenylphenol and T-butyl(meth)acrylate
 IN Yamachika, Mikio, Kuwana, Japan
 Kobayashi, Eiichi, Albany, CA, United States
 Ota, Toshiyuki, Yokkaichi, Japan
 Tsuji, Akira, Yokkaichi, Japan
 PA Japan Synthetic Rubber Co., Ltd., Tokyo, Japan (non-U.S. corporation)
 PI US 5556734 19960917
 AI US 1994-363269 19941223 (8)
 PRAI JP 1993-345792 19931224
 JP 1994-268112 19941007
 DT Utility
 FS Granted
 LN.CNT 1357
 INCL INCLM: 430/270.100
 INCLS: 430/192.000; 430/910.000; 430/921.000
 NCL NCLM: 430/270.100
 NCLS: 430/192.000; 430/910.000; 430/921.000
 IC [6]
 ICM: G03C001-73
 EXF 430/270; 430/326; 430/192; 430/910; 430/921
 CAS INDEXING IS AVAILABLE FOR THIS PATENT.

L6 ANSWER 10 OF 14 USPATFULL on STN

Full Text	Citing References
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AN 95:33997 USPATFULL
 TI Resin composition for aqueous paint
 IN Fujibayahsi, Toshio, Hadano, Japan
 Nagaoka, Haruo, Hiratsuka, Japan
 PA Kansai Paint Co., Ltd., Hyogo, Japan (non-U.S. corporation)
 PI US 5407748 19950418
 AI US 1993-133363 19931008 (8)

PRAI JP 1992-297953 19921009
 JP 1993-32538 19930129
 JP 1993-32587 19930129
 DT Utility
 FS Granted
 LN.CNT 2215
 INCL INCLM: 428/418.000
 INCLS: 523/404.000; 523/414.000; 525/407.000; 525/409.000
 NCL NCLM: 428/418.000
 NCLS: 523/404.000; 523/414.000; 525/407.000; 525/409.000
 IC [6]
 ICM: B32B015-08
 EXF 428/418; 523/404; 523/414; 525/407; 525/409
 CAS INDEXING IS AVAILABLE FOR THIS PATENT.

L6 ANSWER 11 OF 14 USPATFULL on STN

Full Text	Citing References
AN 94:104621 USPATFULL	
TI Resin composition for aqueous paints	
IN Fujibayashi, Toshio, Hadano, Japan	
Nagaoka, Haruo, Hiratsuka, Japan	
PA Kansai Paint Co., Ltd., Hyogo, Japan (non-U.S. corporation)	
PI US 5369151 19941129	
AI US 1993-120787 19930915 (8)	
RLI Division of Ser. No. US 1993-48512, filed on 20 Apr 1993	
DT Utility	
FS Granted	
LN.CNT 1396	
INCL INCLM: 523/414.000	
INCLS: 204/181.400; 204/181.700; 428/418.000	
NCL NCLM: 523/414.000	
NCLS: 204/503.000; 204/504.000; 204/505.000; 428/418.000	
IC [5]	
ICM: C08K003-20	
ICS: C08L063-04	
EXF 523/414; 204/181.4; 204/181.7; 428/418	
CAS INDEXING IS AVAILABLE FOR THIS PATENT.	

L6 ANSWER 12 OF 14 USPATFULL on STN

Full Text	Citing References
AN 94:104620 USPATFULL	
TI Resin composition for aqueous paints	
IN Fujibayashi, Toshio, Hadano, Japan	
Nagaoka, Haruo, Hiratsuka, Japan	
PA Kansai Paint Co., Ltd., Hyogo, Japan (non-U.S. corporation)	
PI US 5369150 19941129	
AI US 1993-48512 19930420 (8)	
PRAI JP 1992-129740 19920424	
DT Utility	
FS Granted	
LN.CNT 1385	
INCL INCLM: 523/414.000	
NCL NCLM: 523/414.000	
IC [5]	
ICM: C08K003-20	
ICS: C08L063-04	
EXF 523/414	
CAS INDEXING IS AVAILABLE FOR THIS PATENT.	

L6 ANSWER 13 OF 14 USPATFULL on STN

Full Text	Citing References
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AN 93:44346 USPATFULL
 TI Phenolic resin and method for preparing same
 IN Ando, Shinji, Nagoya, Japan
 Fukui, Yukio, Nagoya, Japan
 Timuro, Shigeru, Nagoya, Japan
 PA Mitsui Toatsu Chemicals, Inc., Tokyo, Japan (non-U.S. corporation)
 PI US 5216112 19930601
 AI US 1991-745422 19910815 (7)
 PRAI JP 1990-216984 19900820
 JP 1990-216985 19900820
 JP 1990-262984 19901002
 JP 1991-39940 19910306
 DT Utility
 FS Granted
 LN.CNT 951
 INCL INCLM: 528/157.000
 INCLS: 528/129.000; 528/144.000; 528/165.000
 NCL NCLM: 528/157.000
 NCLS: 528/129.000; 528/144.000; 528/165.000
 IC [5]
 ICM: C08G008-04
 ICS: C08G014-04
 EXF 528/129; 528/165; 528/144; 528/157
 CAS INDEXING IS AVAILABLE FOR THIS PATENT.

L6 ANSWER 14 OF 14 USPATFULL on STN

Full Text	CITE REFERENCES
--------------	--------------------

AN 89:87611 USPATFULL
 TI High molecular weight **ortho cresol**-novolak resins and process for
 the preparation thereof using alcoholic or acidic organic solvents
 IN Nakano, Yoshitomo, Mie, Japan
 Kada, Masumi, Mie, Japan
 PA Mitsubishi Petrochemical Co., Ltd., Tokyo, Japan (non-U.S. corporation)
 PI US 4876324 19891024
 AI US 1987-49335 19870513 (7)
 RLI Division of Ser. No. US 1985-741138, filed on 4 Jun 1985, now abandoned
 PRAI JP 1984-116510 19840608
 DT Utility
 FS Granted
 LN.CNT 1236
 INCL INCLM: 528/142.000
 INCLS: 528/144.000
 NCL NCLM: 528/142.000
 NCLS: 528/144.000
 IC [4]
 ICM: C08G008-12
 EXF 528/142; 528/144
 CAS INDEXING IS AVAILABLE FOR THIS PATENT.

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